

Inventor: Li Li et al.

Title: Atomic Layer Deposition Methods of Forming Silicon Dioxide
Comprising Layers

Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with
37 CFR § 1.56. Copies of the cited art are included. No admission is made
regarding whether all the submitted references are prior art.

Respectfully submitted,

Dated: 9-23-03

Attorney: 

Mark S. Matkin
Reg. No. 32,268

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2144	SERIAL NO. Unknown
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Li Li et al.	
				FILING DATE Filed Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS							
*Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
	AA	2001/0024387 A1	09/27/01	Raaijmakers et al.			
	AB	2001/0041250 A1	11/15/01	Werkhoven et al.			
	AC	10/133,947		Vaartstra (as filed)			04/25/2002
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AJ							
	AK							
	AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
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